【Abstract】

A substrate support apparatus includes an upper plate supporting a substrate, a lower plate disposed under the upper plate, an insulating member interposed between the upper plate and the lower plate, an electrode interposed between the upper plate and the insulating member to direct plasma onto the substrate supported by the upper plate, and a heater interposed between the insulating member and the lower plate to heat the substrate supported by the upper plate. The insulating member includes a material having a volume resistance greater than or equal to about 10^6 Ω-cm at a temperature of about 400°C to about 800°C so as to reduce a leakage current between the heater and the electrode.